

# United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
09/785,815	02/16/2001	Yeuk-Fai Edwin Mok	4969/USA/ISM/COPPER/SB 4127			
32588	7590 04/13/2004		EXAMINER			
APPLIED MATERIALS, INC.			MACARTHUR, SYLVIA			
	BLVD. M/S 2061 RA, CA 95050		ART UNIT PAPER NUMBER			
SANTA CLA	KA, CA 75050		1763			

DATE MAILED: 04/13/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

						mr_		
194		Applic	ation No.	Applicant(s)				
		09/785	5,815	MOK ET AL.				
	Office Action Summary	Exami	ner	Art Unit				
			R MacArthur	1763				
Period fo	The MAILING DATE of this commun or Reply	nication appears on	the cover sheet with the	correspondence add	Iress			
A SH THE - Exte after - If the - If NO - Failu Any	IORTENED STATUTORY PERIOD F MAILING DATE OF THIS COMMUN ensions of time may be available under the provision of SIX (6) MONTHS from the mailing date of this come e period for reply specified above is less than thirty (1) of period for reply is specified above, the maximum so are to reply within the set or extended period for repl reply received by the Office later than three months hed patent term adjustment. See 37 CFR 1.704(b).	NICATION. us of 37 CFR 1.136(a). In no amunication. (30) days, a reply within the statutory period will apply an ly will, by statute, cause the	o event, however, may a reply be t statutory minimum of thirty (30) da nd will expire SIX (6) MONTHS fror application to become ABANDON	timely filed  ays will be considered timely.  m the mailing date of this con IED (35 U.S.C. § 133).				
Status								
1)	Responsive to communication(s) fil	led on <u>08 March 20</u>	<u>04</u> .					
2a)□	•	2b)⊠ This action i						
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposit	ion of Claims							
5)	Claim(s) <u>1-8,10,12,13,23,24 and 27</u> 4a) Of the above claim(s) is/a Claim(s) is/are allowed. Claim(s) <u>1-8,10,12,13,23,24 and 27</u> Claim(s) is/are objected to. Claim(s) are subject to restri	are withdrawn from 7-37 is/are rejected	consideration.	4				
Applicati	ion Papers							
10)⊠	The specification is objected to by the The drawing(s) filed on <u>16 February</u> Applicant may not request that any object Replacement drawing sheet(s) including The oath or declaration is objected to	$\frac{\sqrt{2001}}{2001}$ is/are: a) $\boxed{2}$ ection to the drawing (signature) $\boxed{2}$ the correction is required.	s) be held in abeyance. Sequired if the drawing(s) is o	ee 37 CFR 1.85(a). bjected to. See 37 CFF	R 1.121(d).			
	•	by the Exermine	Note the attached one	e rionon or ionni	J. 102.			
	under 35 U.S.C. § 119							
a)l	Acknowledgment is made of a claim  All b) Some * c) None of:  1. Certified copies of the priority  2. Certified copies of the priority  3. Copies of the certified copies application from the Internation	y documents have by documents have be of the priority docu	peen received. Deen received in Applica Iments have been receiv Rule 17.2(a)).	tion No ved in this National S	Stage			
			-					
Attachmen			_			•		
2) 🔲 Notic	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (I mation Disclosure Statement(s) (PTO-1449 or	•	4) Interview Summar Paper No(s)/Mail D 5) Notice of Informal	Date	·152)			
	er No(s)/Mail Date		6) Other:					

Art Unit: 1763

#### **DETAILED ACTION**

1. The finality of the previous office action has been withdrawn. The indicated allowability of claims 3, 11-13, 23, 26, and 34-37 is withdrawn in view of the newly discovered reference(s) to Rattan et al. Rejections based on the newly cited reference(s) follow.

## Claim Rejections - 35 USC § 103

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 1, 2, 4-8, 10, 24, and 27-33 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hey et al (US 6,551,488 in view of Rattan et al (US 4,489,740).

**Regarding Claim 1, 5, 24, and 28:** Hey et al teaches the segmenting of a processing system into wet and dry areas. The mainframe 214 comprises a transfer station 216 (transfer position), a spin-rinse dry (SRD) station 212 (rinse position), and an IBC system 235 (etch position), see col. 5 lines 12-62.

Art Unit: 1763

A plurality of nozzles are described as being articulated to a variety of positions the first nozzles extend fluid onto the top of the substrate while the second nozzles extend fluid onto the bottom of the substrate.

Hey fails to teach a plurality of cooperatively moveable etchant dispense nozzles dispense etchant on the front and backside of the substrate.

Rattan teaches a plurality of cooperatively movable etchant dispense nozzles (18 and 20) wherein the arm and nozzles are configured to dispense etchant on the front and back of the substrate. The nozzles are described as being carried on a common, oscillating arm 22, see col.4 lines 32-37.

The motivation to modify the apparatus of Hey to include nozzles like those of Rattan are that this configuration provides for the uniform etching of the substrate on both sides of the wafer.

**Regarding claim 2:** The wafer orientor 230 (substrate centering hoop) of Hey positions each wafer 234 in a desired orientation to ensure that the wafer is properly processed.

**Regarding claims 4, 27, and 33:** Hey teaches that the unwanted deposits are removed from the edge exclusion zone by the adjustment of the nozzles, see col.8 lines 5-18.

The pedestal actuator 334 rotates the pedestal to spin the substrate and raises and lowers the pedestal. The system of Dordi also adjusts the orientation and placement of nozzles so that the unwanted deposits can be removed along the edge of the substrate to create an edge exclusion zone. The fluid/chemical delivery assembly 2106 comprises one or more nozzles 2150 disposed on one or more dispense arms 2152 which dispenses rinsing fluid and etchant. The dispense arm

Art Unit: 1763

2152 includes one ore more conduits extending through the dispense arm for connecting the nozzle 2150 to an etchant source.

The loading station transfer robot 228 (actuator) also transfers wafer 234.

**Regarding claims 6 and 29**: Hey et al teaches in col. 27 lines 57-64 that slit valve 922 is provided as an assess route for the transfer robot. Fig. 2 illustrates its proximity to the transfer position.

**Regarding claims** 7 and 30: Col. 6 lines 5-8 discusses that the pedestal actuator 334 rotates the pedestal to spin the substrate and raises and lowers the pedestal, this is illustrated as a spindle assembly in Fig. 4.

Regarding claims 8 and 31: Col. 6 lines 13-15 that a vacuum chuck is used.

Regarding claim 32: The articulating member anticipates a dispensing arm.

**Regarding claim 10:** Hey teaches that the unwanted deposits are removed from the edge exclusion zone by the adjustment of the nozzles, see col.8 lines 5-18. It is a matter of intended use that the nozzles dispense etchant rather than rinsing fluid. The nozzles of Hey are inherently capable of dispensing etchant.

## Allowable Subject Matter

Claims 3, 12, 13, 23, and 34-37 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The prior art of record fails to teach or fairly suggest a rotatable a centering hoop rinsing nozzle and a dispensing arm assembly.

Art Unit: 1763

#### Response to Arguments

6. Applicant's arguments with respect to claims 1-8,10,12,13,23,24 and 27-37have been considered but are moot in view of the new ground(s) of rejection.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sylvia R MacArthur whose telephone number is 571-272-1438. The examiner can normally be reached on M-F during the core hours of 8 a.m. and 2 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory L. Mills can be reached on 703-308-1633. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Sylvia R MacArthur Patent Examiner Art Unit 1763

April 2004 Wack